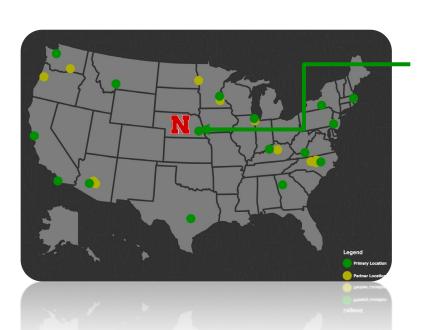
#### NEBRASKA NANOSCALE FACILITY: NNF

### NNCI 2022 Annual Conference Nexus between impactful research & infrastructure development

Christian Binek\*, Jacob John,† Steven Wignall§, Hahn Phan§

\*Director: NNF & NCMN, †Coordinator & Program Manager: NNF, §E/O Coordinator: NNF



NNF NCMN



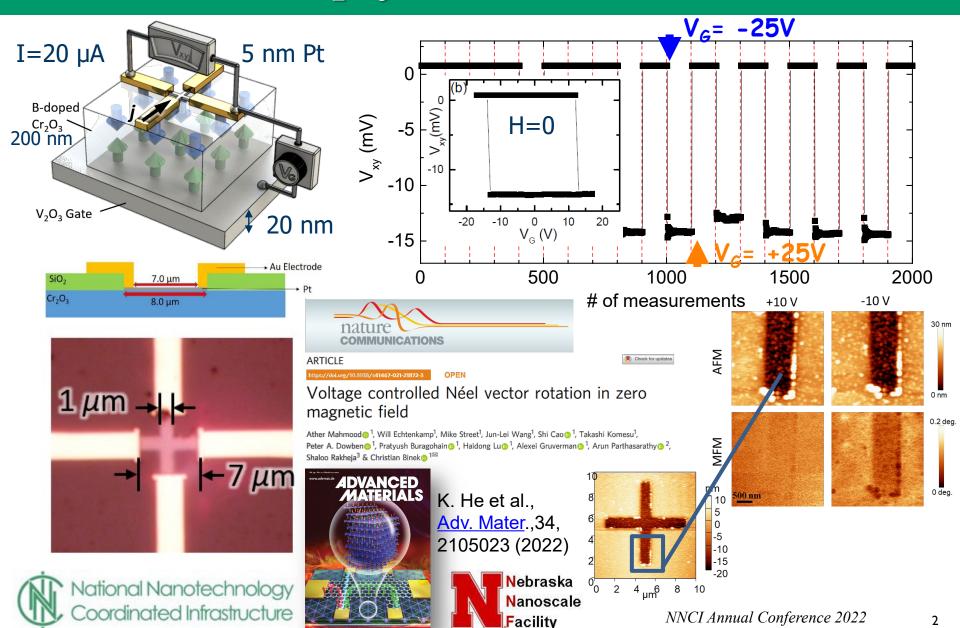
Voelte-Keegan Nanoscience Research Center @ University of Nebraska





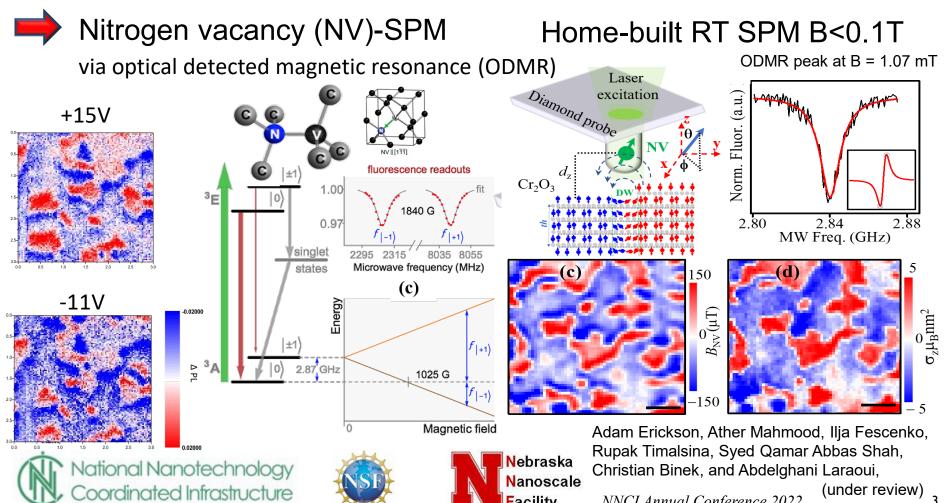


## Zero H-field V-controlled Néel vector rotation in B:Cr<sub>2</sub>O<sub>3</sub>/Pt Hall-bar devices



#### Experimental evidence for switching beyond magnetic force microscopy

MFM measurements ask for more detailed magnetic scanning probe microscopy (SPM)

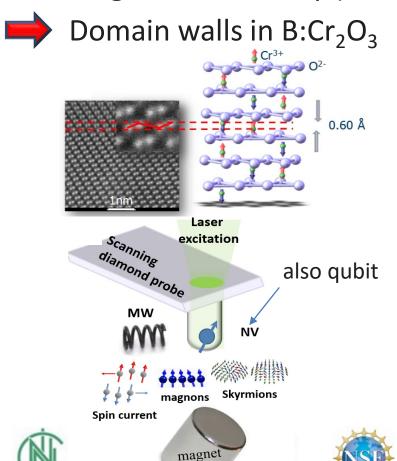


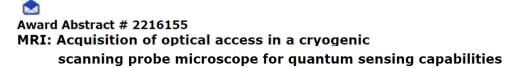
**Facility** 

NNCI Annual Conference 2022

# The case for an NV atomic force and optical confocal microscopes

 Operating from RT down to cryogenic temp at high magnetic fields at unprecedented spatial resolution (< 15 nm) and magnetic sensitivity (< 10 nT Hz-1/2)</li>





NSF Org:	DMR Division Of Materials Research
Awardee:	BOARD OF REGENTS OF THE UNIVERSITY OF NEBRASKA
Initial Amendment Date:	August 17, 2022
Latest Amendment Date:	September 7, 2022
Award Number:	2216155
Award Instrument:	Standard Grant
Program Manager:	Guebre Tessema gtessema@nsf.gov (703)292-4935 DMR Division Of Materials Research MPS Direct For Mathematical & Physical Scien
Start Date:	September 1, 2022



# Microelectronics and the CHIPS and Science Act

- How should NNCI react on the CHIPS Act ?
  - Explore what it entails
    - \$39 B for new chip manufacturing plants
       e.g 2 chip foundry by Intel in the Midwest (central Ohio )
    - \$11 B for R&D
    - Workforce training ...
- Find out what that means for NNCI and a post-NNCI infrastructure
  - Almost certainly big role in workforce development
- At NNF there has been strong emphasis on characterization
  - Strengthen fabrication tools for quantum nanofab







#### New tools for quantum nanofab

For NNF that means



replace 13 year old 30keV e-beam lithography by

a **reliable state-of-the-art lithography tool** (such as Raith EBPG 5150Plus, 100kV e-beam, 50MHz pattern generator, alignment precision <+/- 5nm line width resolution <8nm) allowing high-resolution patterning over large areas and on a large variety of substrates



Workforce training with exposure to:

- nano-electronics,
- nano-photonic
- quantum information science,
- nano-mechanics,
- ano-biology







